



CO₂ Capture and Utilization and Molecular Simulation

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Message from the Guest Editors

This Special Issue, entitled "CO₂ Capture and Utilization and Molecular Simulation", aims to gather high-quality contributions that address the most recent and innovative advancements in CCU technology and molecular simulation-assisted CCU process development. Topics include, but are not limited to, the following:

1. The development of models or simulations for CO₂ capture and utilization
2. The innovative development of CO₂ capture and utilization technologies.
3. Multiscale molecular simulation for the CO₂ capture process
4. The process design, optimization and economic evaluation of an CO₂ capture system

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Message from the Editor-in-Chief

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